# Monthly LabAdviser/Process2Share update: 26/6 2015

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| Updated Subject  | Contributor | Link to the updated pages |
| **Si etching in RIE2**Test using recipe OH\_PolyA with a range of different silicon loads. | **Pernille V. Larsen @danchip** | [Etching\_of\_Silicon/Si\_etch\_using\_RIE1\_orEtching\_of\_Silicon/Si\_etch\_using\_RIE1\_or\_RIE2/RIE2\_Travka\_results](http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Etch/Etching_of_Silicon/Si_etch_using_RIE1_or_RIE2/Specific_Process_Knowledge/Etch/Etching_of_Silicon/Si_etch_using_RIE1_or_RIE2/RIE2_Travka_results) |
| **Spin coater: RCD8**Info on the new spin coater RCD8 has been added. | **Thomas Anhøj @danchip** | [Lithography/Coaters#Spin\_Coater:\_RCD8](http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Lithography/Coaters#Spin_Coater:_RCD8) |
| **PECVD2**New QC recipe has been implemented. New names for oxide recipes | **Berit G. Herstrøm @danchip** | [Deposition\_of\_Silicon\_Oxide\_using\_PECVD](http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_Silicon_Oxide/Deposition_of_Silicon_Oxide_using_PECVD) |
| **Process2Share: 3-week project**Hydrogen Annealing for Removal of Scallops after DRIE | **3-week students: Daniel Angyaogu, Emil Ludvigsen****Supervisors:****Pernille V. Larsen, Mikkel Mar @danchip**  | [Projects,\_Theses\_and\_Papers/3-week\_courses](http://process2share.danchip.dtu.dk/index.php/Projects%2C_Theses_and_Papers/3-week_courses) |
| **CEN SEM**SEM FEI Quanta 200 3D equipment page has been created and it is in the SEM comparison table. The SEM is positioned at CEN. | **Zoltan Imre Balogh @CEN** | [Characterization/SEM\_FEI\_QUANTA\_200\_3D](http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Characterization/SEM_FEI_QUANTA_200_3D)[SEM:\_Scanning\_Electron\_Microscopy](http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Characterization/SEM%3A_Scanning_Electron_Microscopy) |

# Equipment Manuals updated in LabManager:

As an approved user on a piece of equipment you have to make sure you have read and understood the latest version of the manual before using the equipment.

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|  | **Manual for EVG NIL** |
|  | **Manual for Aligner\_6inch\_ EVG620.** |
|  | **Manual Polymer Spinner\_OPTIcoat SB20+.** |
| http://d4.danchip.dtu.dk/D4Doc/res/menu/user_bullet.gif | **Manual for HMDS\_Vapor Prime Oven Star2000** |
| http://d4.danchip.dtu.dk/D4Doc/res/menu/user_bullet.gif | **Manual for Plasma Asher2\_Model 300 Plasma Processor** |
| http://d4.danchip.dtu.dk/D4Doc/res/menu/user_bullet.gif | **Manual for SSE Spinner\_ Maximus 804.** |
| http://d4.danchip.dtu.dk/D4Doc/res/menu/user_bullet.gif | **Manual for KS Aligner\_ MA6** |
|  | **Manual for SU-8 Developer Bench** |
|  | **Manual for Inclined UV-lamp** |
|  | **Manual for Oven 110-250C** |
| http://d4.danchip.dtu.dk/D4Doc/res/menu/user_bullet.gif | **Manual for Oven 90C** |
| http://d4.danchip.dtu.dk/D4Doc/res/menu/user_bullet.gif | **Manual for Fine Strip**  |
| http://d4.danchip.dtu.dk/D4Doc/res/menu/user_bullet.gif | **Manual for Rough Strip**  |
| http://d4.danchip.dtu.dk/D4Doc/res/menu/user_bullet.gif | **Manual for Lift-off wet bench** |
| http://d4.danchip.dtu.dk/D4Doc/res/menu/user_bullet.gif | **Manual for Lift-off (4", 6")** |
|  | **Manual for Aligner: MA6 - 2** |
|  | **Manual for LPCVD TEOS furnace** |
|  | **Manual for Picosun ALD** |
|  | **Manual for Resist Pyrolysis Furnace** |
| http://d4.danchip.dtu.dk/D4Doc/res/menu/user_bullet.gif | **Manual for Nikon SMZ 1500 optical microscope** |
| http://d4.danchip.dtu.dk/D4Doc/res/menu/user_bullet.gif | **Manual for Zeiss Axiotron 2 optical microscope** |
|  | **Manual for III-V Plasma Asher\_ Pico.** |

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